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APPARATUS FOR USE IN CLEANING WAFERS

Abstract of the Disclosure

A semiconductor wafer scrubbing and drying apparatus is capable processing wafers in a vertical orientation from start to finish. The apparatus moves the wafers in a generally vertical direction from an entry station of the apparatus to a dryer of the apparatus. The wafers enter the apparatus in a cassette and exit in another cassette in the same order as they were in the entry cassette to preserve individual wafer identity. The apparatus is constructed so that the compartment in which the wafers are handled is isolated and the components handling the wafers in that compartment are made of a fluorinated plastic. The actuators driving the motion of the wafer handling components are located in another compartment. A rinsing device in the wafer handling compartment is activated and deactivate for rinsing one of the wafers without the use of valves in the rinse line.

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